ISTITUTO NAZIONALE DI FISICA NUCLEARE LABORATORI DI SUPERCONDUCTIVITA UNIVERSITY OF FERRARA DEPARTMENT OF PHYSICS "Technologies for accelerator and targets in nuclear physics"

#### Construction of an innovative cylindrical magnetron sputtering source for HIE-ISOLDE superconductive Nb/Cu QWRs

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# Content

- HIE ISOLDE project
- Quarter wave resonator cavity (QWR) for ISOLDE project
- The aim of the phD Project
- Development at LNL (2012-2013) and last results
- Conclusions and further work





#### HIE ISOLDE project



#### **QWRs** cavities



### The aim of the PhD. project



#### Coat Copper Quarter Wave Resonator Cavities with Nb thin film





### Magnetron sputtering technique







• Assembly of the system





• Sputtering depositions











• Sputtering depositions

















• The results







- The aim for the 2<sup>nd</sup> year
- Perform the deposition of Nb over the cavity.
  Moreover, measure the superconductive properties (RRR, Tc)









• The aim for the 2<sup>nd</sup> year











• The Results



The deposition was performed with a base vacuum of 4,2x10<sup>-8</sup> mbar using the following parameters: Power= P 1\* Sputtering pressure= p1\* Time: 25 min, time intervals of 5 (\*)Reserved for privacy INFN





• The Results









 Residual resistance ratio (RRR) and Critical temperature (Tc)











Quartz sample

 $RRR = \frac{R(300K)}{R(10K)}$ 









Sample	1	3	8	11	15	18
Thickness (μm)	0,88	1,12	0,53	0,31	0,75	0,62
Tc (K)	7,44	8,7	8,7	7,6	7,7	5,8
RRR	1,77	3	2,92	1,82	1,99	1,29

• The Results



Sample	1	3	8	11	15	18
Thickness (µm)	0,57	0,58		0,86	0,62	0,33
Тс (К)	8,2	8,8		7,05	8,51	8,32
RRR	2,18	2,89		1,03	2,07	2,02

• The Results

A new deposition was performed a deposition using the following parameters: Psputtering= p 2\* Power= P2\* Sputtering time: 30 min with intervalous of time

We took the 15<sup>th</sup> position as a parameter to understand the behavior of the procces, in order to improve the RRR value.





• The Results

Sample	-11	1	3	8	11	15	18
RRR	x	Х	3,3	3,73	Х	3,4	3,6
Tc (K)			8,76	8,72		8,81	8,78







• The Results

Psputtering= p 3\* Power = P3\* Sputtering time: 30 min with intervalous of time of 5 min

Sample	-11	1	3	8	11	15	18
RRR	x	3,2	Х	х	Х	5,2	6
Tc(K)		8,84				9,1	9,17







Was performed another deposition with the following parameters: Psputtering= p4\* Power = P4\* Sputtering time: 30 min with intervalous of time of 5 min.

As we saw in the previous deposition the RRR value is increasing while the power is higher

Sample	-11	1	3	8	11	15	18
RRR	Х	Х	Х	Х	Х	9,24	Х
Tc (K)						9,34	







In order to improve the vacuum, was placed on the top of the chamber a Nb magnetron to be used as a getter. Also was performed

a new deposition keeping the same parameters used before:

Power= P5\* Psputtering= p5\* Time: 30min The deposition was done heating the cavity @350°C.

Sample	-11	1	3	8	11	15	18
RRR	Х	Х	Х	Х	Х	10,41	х
Tc (K)						9,3	















After was done the deposition inside the cavity, using the Magnetron Sputtering Power supply, with g the following parameters:

> Initial Vacuum Pressure: 4x10<sup>-8</sup> mbar Power = P6\* Sputtering pressure = p6\* Time: 30 min Cavity temperature: 380°C

Sample	-11	1	3	8	11	15	18
RRR	х	Х	12,9	19,6	Х	12,7	13,4
Tc (K)			9,13	9,21		9,4	9,33







2 Power supply will be connected in order to increase the power during the deposition. The highest power that we can reach is P6\*.

Also will be added to the system 4 more lamps outside the cavity to improve the uniformity of the heating along the cavity during the sputtering process.





















Initial Vacuum Pressure: 4x10<sup>-8</sup> mbar Power = P7\* Sputtering pressure = p7\* Time: 30 min Cavity temperature: (inside and outside the cavity) 300°C

Sample	-11	1	3	8	11	15	18
RRR	x	Х	12,9	14	x	22	27
Tc (K)			9,13	9,19		9,33	9,28













### Nowadays







Power= P8\* Sputtering pressure= p8\* Time: 30 min Cavity temperature: (inside and outside the cavity) 300°C



#### Nowadays



Sample	-11	1	3	8	11	15	18
RRR				61			
Тс (К)				9,3			







### Conclusions

-The vacuum system was successfully assembled and is available for thin film deposition.

- The uniformity of the Nb thin film along the cavity is quiet good, however we are trying to improve this results with another magnetic field source

- The RRR is higher if the substrate is heated during the sputtering process

-Increasing the power of deposition the RRR values are higher along the cavity





### Further works

-Deposit the niobium film onto copper plates in order to close the QWR cavity.

-Perform the deposition directly with the Niobium cathode onto copper cavities.

-Design the cryostat and the RF system in order to measure the superconductive properties of the cavities

-Perform the measure of superconductive properties (Tc ,RRR and Q value)





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### Thanks for your attention





